P. 01

SEP 1 6 2004

REPLY UNDER 37 C.F.R. § 1.116 EXPEDITED PROCEDURE **EXAMINING GROUP 1765**

CMERCED BY
REES.

PATENT 5298-06900/PM01027

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Schwarz

Scrial No. 10/074,888

Filed: February 13, 2002

For:

REDUCING DEFECT FORMATION

WITHIN AN ETCLEED

SEMICONDUCTOR TOPOGRAPHY

Group Art Unit: 1765 Examiner: Deo, D.

Any. Dkt. No. 5298-06900

I bereby certify that this correspondence is being transmitted via facelmills or deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope subjected to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313, on the date indicated below:

September 16, 2004

Date

AMENDMENT; RESPONSE TO FINAL OFFICE ACTION DATED JULY 23, 2004

Mall Stop AF Commissioner for Palents P.O. Box 1450 Alexandrio, VA 22313

Dear Sirl Madam:

This paper is submitted in response to the final Office Action dated July 23, 2004 to further highlight reasons why the application is in condition for allowance.

Amendments to the Specification begin on page 2 of this paper.

Amendments to the Claims are reflected in the listing of claims which begins on page 3 of this paper.

Remarks begin on page 7 of this paper.

SN 10/074,888 Response to Final Office Action Mailed 7/23/2004

Page 1 of 13

PAGE 1113" RCVD AT 91 92004 2:59:14 PM [Eastern Daylight Time]" SVR:USPTO-EFXEF-14" DHIS:8729306" CSID:5127031250 "DURATION (mm-ss):08-08